IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method for inspecting an insulating layer deposited or planarized on a substrate in fabrication processes of semiconductor with a library of optic images, the method comprising the steps of:

collecting standard data for thickness of the insulating layer;
collecting standard data for an optic image of the insulating layer;
making a library by matching standard data for the thickness and the optic
image collected on a same location on the substrate; and

inspecting the insulating layer with the library.

- 2. (Original) The method as defined by claim 1, wherein the standard data for the thickness is data for a particular region or the whole of the wafer.
- 3. (Original) The method as defined by claim 1, wherein the standard data for the optic image is data for a particular region or the whole of the wafer.
- 4. (Original) The method as defined by claim 1, wherein the optic image is stored in analog or digital image.
- 5. (Currently Amended) The method as defined by claim 1, wherein the step of making a library is characterized in that includes making a library such that each optic image for the region represented by each thickness data is determined and a continuous image library for each thickness is constructed.
- 6. (New) A method for inspecting an insulating layer deposited or planarized on a substrate in fabrication processes of semiconductor with a library of optic images, the method comprising:

collecting thickness data of the insulating layer at a plurality of locations on the substrate;

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collecting optic image data of the insulating layer for said plurality of locations on the substrate;

correlating the optic image data to the thickness data for each of said plurality of locations;

creating a library by matching the optic image data to the thickness data for each of said plurality of locations; and

inspecting the insulating layer for each of said locations with the library.